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Pty. Docket No. PIA31069/ANS/US

IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF:

Sang Hun Oh

: GROUP ART UNIT:

SERIAL NO: 10/751,184

:

FILED: December 30, 2003

: EXAMINER:

FOR: Method for Etching a Metal Layer in a Semiconductor Device

I hereby certify that this document is being deposited with the United States Postal Service as first class mail in an envelope addressed to Commissioner for Patents, Washington, D.C. 20231, on January 27, 2004.

By:

Andrew D. Fortney, Ph.D.CLAIM FOR PRIORITY UNDER 35 U.S.C. 119(a)-(b) AND 37 C.F.R. 1.55

COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20231

SIR:

Applicant respectfully requests under the Paris Convention for the Protection of Intellectual Property the benefit of the filing date of the prior foreign application(s) identified below:

<u>Serial No.</u>	<u>Filing Date</u>	<u>Country of Filing</u>
10-2002-0086802	December 30, 2002	Republic of KOREA

A certified copy of the above-identified priority application is attached.

Respectfully submitted,

Andrew D. Fortney, Ph.D.
Reg. No. 34,600

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별첨 사본은 아래 출원의 원본과 동일함을 증명함.

This is to certify that the following application annexed hereto
is a true copy from the records of the Korean Intellectual
Property Office.

출원 번호 : 10-2002-0086802
Application Number

출원 년 월 일 : 2002년 12월 30일
Date of Application DEC 30, 2002

출원인 : 아남반도체 주식회사
Applicant(s) ANAM SEMICONDUCTOR.. Ltd.



2003 년 10 월 10 일

특 허 청

COMMISSIONER

